

## ABSTRACT OF THE DISCLOSURE

A plasma reactor including a process chamber, a holding structure constructed arranged to hold a plasma source assembly and a support structure constructed and arranged to support a chuck assembly. The holding structure at least partially constitutes a wall of said vacuum chamber. The support structure supporting or holding the chuck assembly can be coupled to a lift mechanism which can raise or lower the chuck assembly relative to the plasma source assembly. The lift mechanism can be disposed above or below the process chamber.